SPECIALTY GASES & ENGINEERED MATERIALS

ProE-Vap® 100 Delivery System

Effective delivery of solid materials

The ProE-Vap® 100 delivery system is designed for solid precursors used in Atomic Layer Deposition (ALD) and Chemical Vapor Deposition (CVD) processes. It provides a stable mass flux for a wide variety of solid materials used for current and future technology nodes. Solid precursors are difficult to deliver consistently into deposition chambers due to their low vapor pressure and limited thermal stability. The ProE-Vap system overcomes these problems and offers a solution that is unmatched in the industry.

The ProE-Vap delivery system allows for higher transport of solid precursors at lower temperatures more consistently than other vaporizers, thus reducing cost of ownership for ALD and CVD.

It minimizes chemical concentration drifts, allowing for higher wafer throughput with less tool downtime. The ProE-Vap has demonstrated high reliability and robust performance in high-volume manufacturing environments since 2008. It supports delivery of a variety of inorganic and transition metal precursors required in the fabrication of highly complex microelectronic device fabrication.

Available in multiple configurations for installation on different OEM tool sets.

APPLICATIONS

- Atomic layer deposition
- Metal barriers and electrodes
- High-κ capacitors and gate dielectrics
- Fluorine-free tungsten (FFW)



FEATURES & BENEFITS

- Innovative designed ampoule for solid precursor delivery
- Delivers higher mass flux at lower temperature
- Supports pneumatic and manual valve options
- Outstanding overall
 performance with consistent
 flux over the vaporizer lifetime
- Proven for multiple solid precursors used in semiconductor applications and can be used for other emerging technologies, such as LED

- Enables efficient usage of precursor and minimizes decomposition from overheating
- Compatible with several OEM tools; supports developmental high volume wafer processing
- Reduces cost of ownership



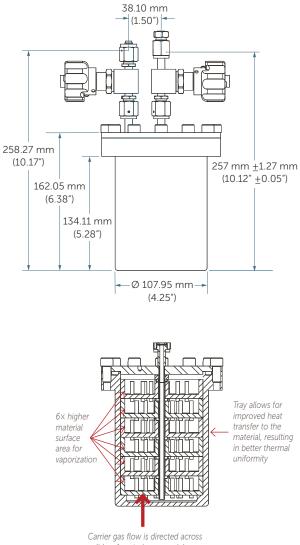
SPECIFICATIONS

Performance Specifications

Maximum	200°C — 250°C (392°F — 482°F)
temperature	depending on configuration
Maximum pressure	100 psig at operating temperature

Facilities Specifications for Camp-003012 Configuration

Overall dimensions	258.27 mm H × Ø139.7 mm W (10.17" H × 5.5" W)	
Gas inlet:	Location	Center axis
	Fitting type	$^{1}\!\!/_{4}$ " female VCR®
	Height	257 mm (10.12")
Gas outlet	Location	1.5" off center axis
	Fitting type	¹ /4" male VCR
	Height	258.27 mm (10.17")
	Material	316L SS
	Surface finish	<u>≤</u> 10 Ra
Recommended carrier gases	UHP He (Helium) UHP N ₂ (Nitrogen)	5
-	Head Gas	5 psi He



DIMENSIONS

solid surface to increase pick-up rate of vaporizing material

FOR MORE INFORMATION

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